

ABSTRACT

CLEANING AGENT COMPOSITION FOR REMOVING RESIN MASK

In one aspect, provided is a cleaning composition with high resin mask removal capability.

An aspect of the present disclosure relates to a cleaning composition for stripping a resin mask. The cleaning composition contains a polyhydric alcohol (component A), amines (component B), and an organic solvent (component C) with a Hansen solubility parameter, SP value, of 18 to 33 MPa^{1/2}, excluding the component A and the component B. The mass ratio A/B of the component A to the component B is 2 or more and 8 or less. The component C is at least one selected from the group consisting of a sulfur-containing compound and a nitrogen-containing compound.